

15.38/5796

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re the Application of:	)	Group Art Unit: 1763
NAMOSE.	)	
Serial No. 09/805,382	)	Examiner: Hassanzadeh, Parviz
Filed: March 13, 2001	)	
For: METHOD OF PROCESSING PFC AND	)	
APPARATUS FOR PROCESSING PFC	)	

**UNOFFICIAL COMMUNICATION TO EXAMINER - NOT TO BE ENTERED**

via facsimile (703) 872-9560

Examiner Hassanzadeh,

As we discussed earlier this week, below you will find new proposed claims 9-20 for this application. I can submit these claims in a formal Preliminary Amendment after you have reviewed them. I will propose to cancel the pending claims and insert claims 9-20 in the Preliminary Amendment. There are also some informalities in the specification that will be corrected either in the Preliminary Amendment or in a subsequent Amendment. I can be reached by telephone at (310) 871-8448.

The proposed new method claims 9-20 are as follows:

9. A method for processing a fluoride compound gas that is used in a device manufacturing process, comprising:

- after the fluoride compound gas is used under a reduced pressure, delivering the fluoride compound gas to an area at atmospheric pressure;
- adding a reactive material to the fluoride compound gas at atmospheric pressure;
- performing a plasma process on the fluoride compound gas and the reactive material at atmospheric pressure and generating a reaction product including a polymer.

10. A method for processing a fluoride compound gas according to claim 9, wherein the reactive material includes a gas selected from the group of a paraffin hydrocarbon and an alcohol.

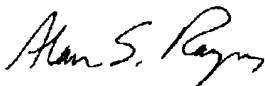
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11. A method for processing a fluoride compound gas according to claim 9, wherein the fluoride compound gas includes fluorine and a material selected from carbon and silicon.
12. A method for processing a fluoride compound gas according to claim 9, wherein the fluoride compound gas is selected from the group consisting of  $\text{CF}_4$ ,  $\text{C}_2\text{F}_6$ ,  $\text{C}_4\text{F}_8$  and  $\text{SF}_6$ .
13. A method for processing a fluoride compound gas according to claim 10, wherein the fluoride compound gas includes fluorine and a material selected from carbon and silicon.
14. A method as in claim 9, further comprising delivering the reaction product to a chamber in which the reaction product can flow in circular movements and the polymer in the reaction product can accumulate in the chamber.
15. A method as in claim 9, wherein the chamber includes a cyclone region where the reaction product flows in circular movements and first and second partition doors adapted to be opened and closed, wherein the second partition door is separated from the cyclone region by the first partition door when the first partition door is closed.
16. A method as in claim 15, wherein the polymer in the reaction product accumulates on the first partition door when the first partition door is closed, and wherein the polymer reaction product accumulates on the second partition door when the first partition door is opened and the second partition door is closed.
17. A method as in claim 15, comprising:  
closing the first partition door and accumulating the polymer in the reaction product on the first partition door;  
opening the first partition door while the second partition door is closed and then transferring the polymer accumulated on the first partition door to the second partition door;  
closing the first partition door and then opening the second partition door and removing the transferred polymer from the second partition door.

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18. A method for processing a fluoride compound gas that is used in a device manufacturing process, comprising:
- after the fluoride compound gas is used under a reduced pressure, delivering the fluoride compound gas to an area at atmospheric pressure;
  - adding a material selected from the group consisting of water and oxygen to the fluoride compound gas at atmospheric pressure;
  - performing a plasma process at atmospheric pressure on the fluoride compound gas and the material to decompose the fluoride compound gas.
19. A method for processing a fluoride compound gas according to claim 17, wherein the fluoride compound gas includes fluorine and a material selected from carbon and silicon.
20. A method for processing a fluoride compound gas according to claim 18, wherein the fluoride compound gas is selected from the group consisting of  $\text{CF}_4$ ,  $\text{C}_2\text{F}_6$ ,  $\text{C}_4\text{F}_8$  and  $\text{SF}_6$ .

Respectfully submitted,



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